

Semiconductor Materials and Devices

(반도체 재료 및 소자)

Chapter 7. The PN junction

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PN Junction

Basic structure in most semiconductors

Metallurgical junction

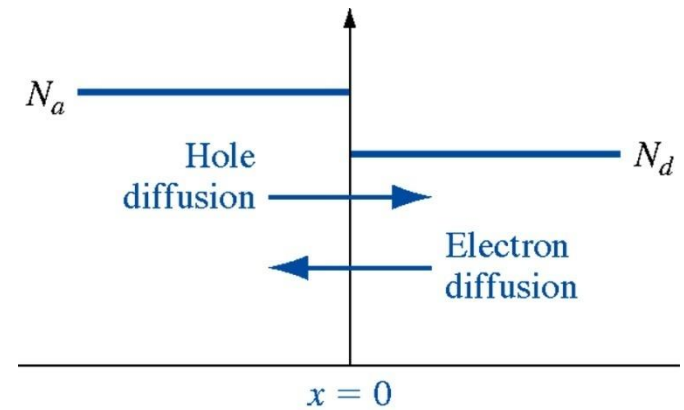
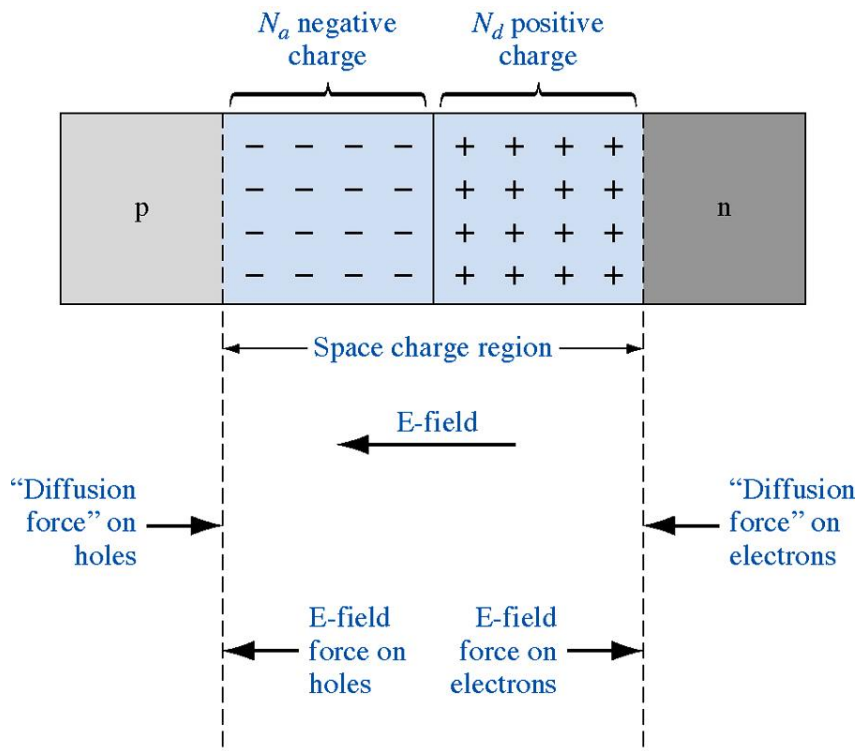
Step junction (abrupt junction)

Space charge region (depletion region)

Diffusion force vs. Electric field



Metallurgical junction



Built-in Potential Barrier

: prevent diffusion flow

$$V_{bi} = |\phi_{Fn}| + |\phi_{Fp}|$$

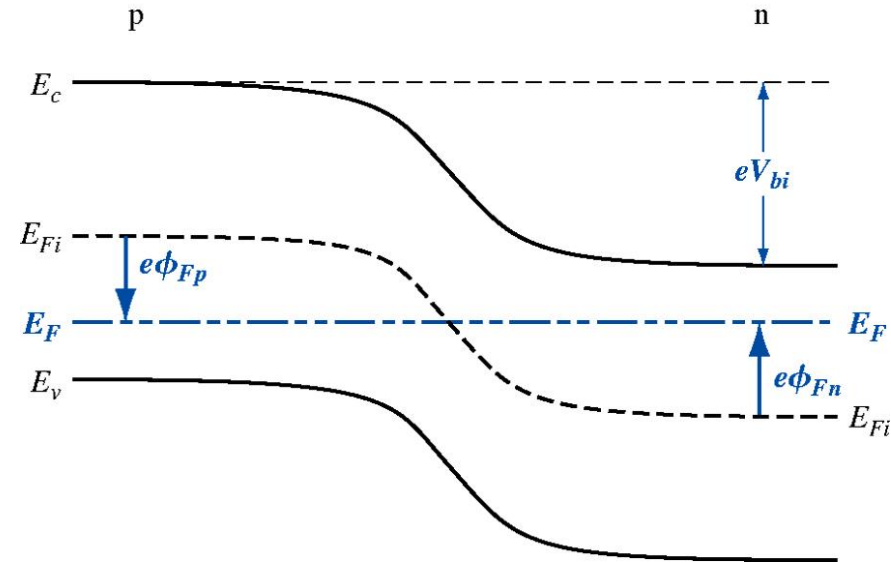
$$\begin{aligned} n_0 &= N_c \exp\left[\frac{-(E_c - E_F)}{kT}\right] = n_i \exp\left[\frac{E_F - E_{Fi}}{kT}\right] \\ &= n_i \exp\left[\frac{-(e\phi_{Fn})}{kT}\right] \quad e\phi_{Fn} = E_{Fi} - E_F \end{aligned}$$

$$\Rightarrow \phi_{Fn} = \frac{-kT}{e} \ln\left(\frac{N_d}{n_i}\right)$$

$$p_0 = N_a = n_i \exp\left[\frac{E_{Fi} - E_F}{kT}\right] \Rightarrow \phi_{Fp} = +\frac{kT}{e} \ln\left(\frac{N_a}{n_i}\right)$$

$$e\phi_{Fp} = E_{Fi} - E_F$$

$$V_{bi} = \frac{kT}{e} \ln\left(\frac{N_a N_d}{n_i^2}\right) = V_t \ln\left(\frac{N_a N_d}{n_i^2}\right)$$



Calculation of E-field

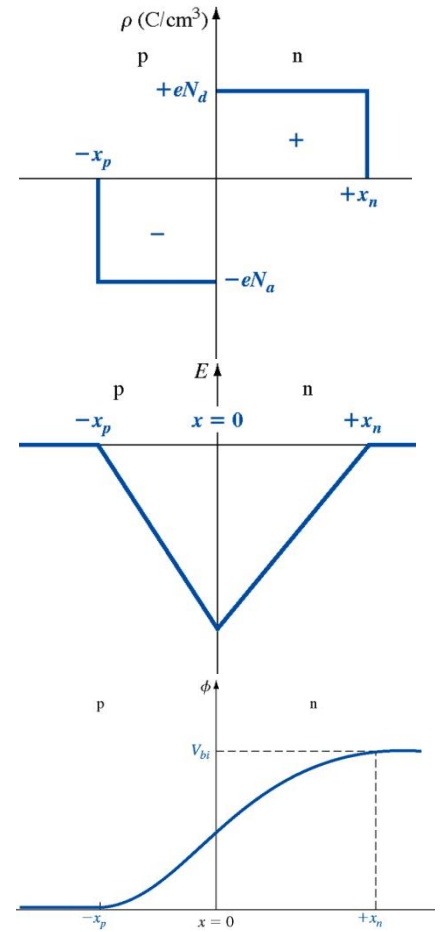
Poisson's equation: $\frac{d^2\phi(x)}{dx^2} = \frac{-\rho(x)}{\epsilon_s} = -\frac{dE(x)}{dx}$ $\phi(x)$: electric potential
 $E(x)$: electric field $\rho(x)$: charge density

$$\left. \begin{aligned} \rho(x) &= -eN_a & -x_p < x < 0 \\ \rho(x) &= eN_d & 0 < x < x_n \end{aligned} \right\} \begin{aligned} E &= \int \frac{\rho(x)}{\epsilon_s} dx = - \int \frac{eN_a}{\epsilon_s} dx = \frac{-eN_a}{\epsilon_s} x + C_1 \\ E &= \int \frac{(eN_d)}{\epsilon_s} dx = \frac{eN_d}{\epsilon_s} x + C_2 \end{aligned} \right\}$$

$$\left. \begin{aligned} E &= \frac{-eN_a}{\epsilon_s} (x + x_p) & -x_p \leq x \leq 0 \\ E &= \frac{-eN_d}{\epsilon_s} (x_n - x) & 0 \leq x \leq x_n \end{aligned} \right\} N_a x_p = N_d x_n$$

$$\left. \begin{aligned} \phi(x) &= - \int E(x) dx = \int \frac{eN_a}{\epsilon_s} (x + x_p) dx \\ \phi(x) &= \int \frac{eN_d}{\epsilon_s} (x_n - x) dx \end{aligned} \right\} \begin{aligned} \phi(x) &= \frac{eN_a}{\epsilon_s} \left(\frac{x^2}{2} + x_p \cdot x \right) + C'_1 \\ \phi(x) &= \frac{eN_d}{\epsilon_s} \left(x_n \cdot x - \frac{x^2}{2} \right) + C'_2 \end{aligned} \right\}$$

$$\left. \begin{aligned} C'_1 &= \frac{eN_a}{2\epsilon_s} x_p^2 \\ C'_2 &= \frac{eN_a}{2\epsilon_s} x_p^2 \end{aligned} \right\} \begin{aligned} \phi(x) &= \frac{eN_a}{2\epsilon_s} (x + x_p)^2 & (-x_p \leq x \leq 0) \\ \phi(x) &= \frac{eN_d}{\epsilon_s} \left(x_n \cdot x - \frac{x^2}{2} \right) + \frac{eN_a}{2\epsilon_s} x_p^2 & (0 \leq x \leq x_n) \end{aligned} \right\} V_{bi} = |\phi(x = x_n)| = \frac{e}{2\epsilon_s} (N_d x_n^2 + N_a x_p^2)$$



Space Charge Width

Distance that the space charge region extends from the metallurgical junction

$$\begin{aligned}
 N_a x_p = N_d x_n &\rightarrow x_p = \frac{N_d x_n}{N_a} \\
 V_{bi} = |\phi(x = x_n)| &= \frac{e}{2\epsilon_s} (N_d x_n^2 + N_a x_p^2)
 \end{aligned}
 \left. \begin{array}{l} \\ \\ \end{array} \right\}
 \begin{aligned}
 x_n &= \left\{ \frac{2\epsilon_s V_{bi}}{e} \left[\frac{N_a}{N_d} \right] \left[\frac{1}{N_a + N_d} \right] \right\}^{1/2} \\
 x_p &= \left\{ \frac{2\epsilon_s V_{bi}}{e} \left[\frac{N_d}{N_a} \right] \left[\frac{1}{N_a + N_d} \right] \right\}^{1/2}
 \end{aligned}$$

$$W = x_n + x_p \quad W = \left\{ \frac{2\epsilon_s V_{bi}}{e} \left[\frac{N_a + N_d}{N_a N_d} \right] \right\}^{1/2}$$

Example 7.2 : Consider silicon pn junction at $T = 300\text{K}$ with $N_a = 10^{16} \text{ cm}^{-3}$ and $N_d = 10^{15} \text{ cm}^{-3}$

$$\begin{aligned}
 W &= \left\{ \frac{2\epsilon_s V_{bi}}{e} \left[\frac{N_a + N_d}{N_a N_d} \right] \right\}^{1/2} \\
 &= \left\{ \frac{2(11.7)(8.85 \times 10^{-14})(0.635)}{1.6 \times 10^{-19}} \left[\frac{10^{16} + 10^{15}}{(10^{16})(10^{15})} \right] \right\}^{1/2} \\
 &= 0.951 \times 10^{-4} \text{ cm} = 0.951 \mu\text{m}
 \end{aligned}$$

$$E_{\max} = \frac{-eN_d x_n}{\epsilon_s} = \frac{-(1.6 \times 10^{-19})(10^{15})(0.864 \times 10^{-4})}{(11.7)(8.85 \times 10^{-14})} = -1.34 \times 10^4 \text{ V/cm}$$

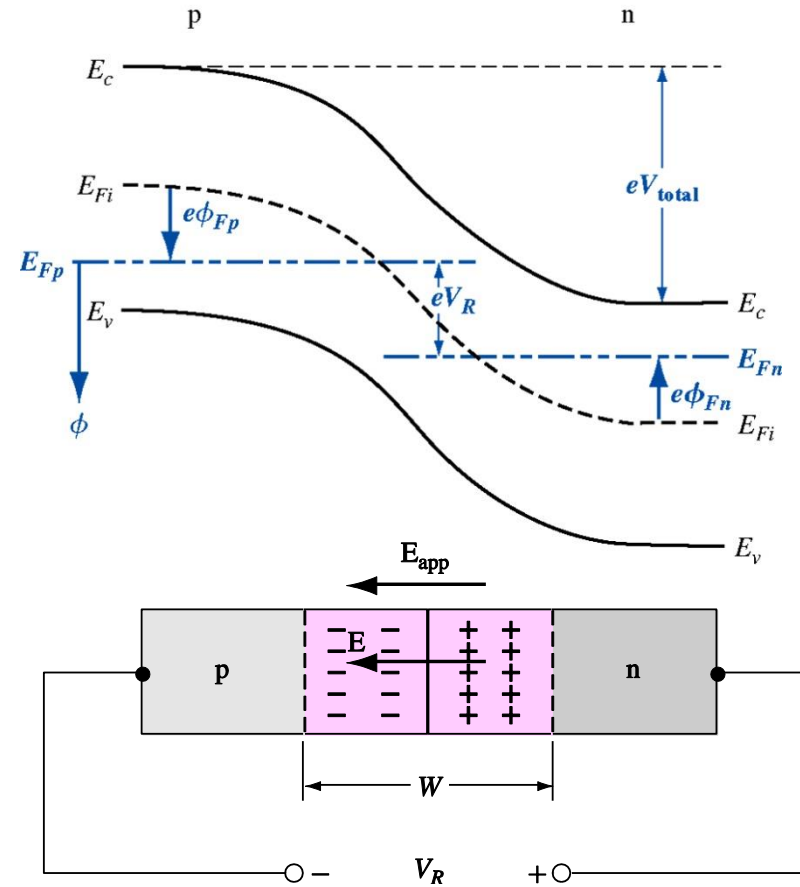
Reverse Bias : a positive voltage is applied to the n region with respect to the p region.

→ Fermi level is no longer constant through the system.
(quasi-Fermi level !)

$$V_{\text{total}} = |\phi_{Fn}| + |\phi_{Fp}| + V_R \quad V_{\text{total}} = V_{bi} + V_R$$

The electric fields in the neutral p and n regions are essentially zero, or at least very small !!

$$W = \left\{ \frac{2\epsilon_s(V_{bi} + V_R)}{e} \left[\frac{N_a + N_d}{N_a N_d} \right] \right\}^{1/2}$$



Example 7.2 : A silicon pn junction at $T = 300\text{K}$ with $N_a = 10^{16} \text{ cm}^{-3}$ and $N_d = 10^{15} \text{ cm}^{-3}$. Let $V_R = 5\text{V}$.

$$W = \left\{ \frac{2(11.7)(8.85 \times 10^{-14})(0.635 + 5)}{1.6 \times 10^{-19}} \left[\frac{10^{16} + 10^{15}}{(10^{16})(10^{15})} \right] \right\}^{1/2}$$

$$W = 2.83 \times 10^{-4} \text{ cm} = 2.83 \mu\text{m}$$

Junction Capacitance

Separated positive and negative charges across the depletion region. → Capacitance !!

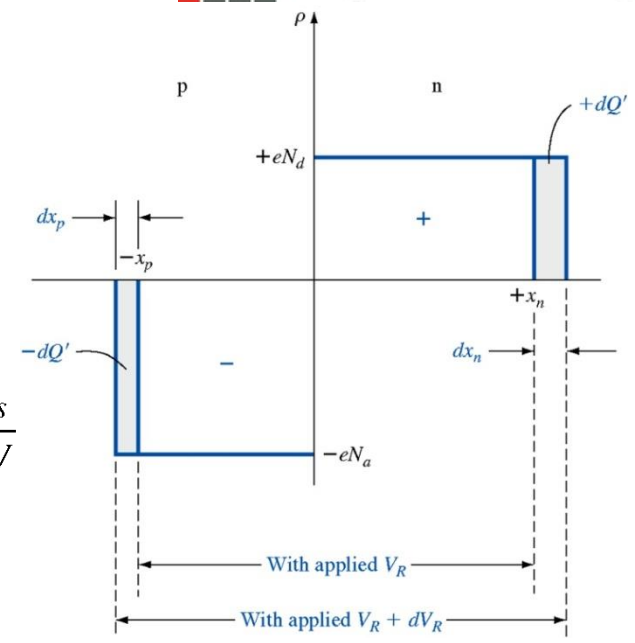
$$C' = \frac{dQ'}{dV_R} \quad \text{where} \quad dQ' = eN_d dx_n = eN_a dx_p$$

$Q' : \text{C/cm}^2, C' : \text{F/cm}^2$

$$C' = \frac{dQ'}{dV_R} = eN_d \frac{dx_n}{dV_R} \Rightarrow C' = \left\{ \frac{e\epsilon_s N_a N_d}{2(V_{bi} + V_R)(N_a + N_d)} \right\}^{1/2} = \frac{\epsilon_s}{W}$$

$$x_n = \left\{ \frac{2\epsilon_s(V_{bi} + V_R)}{e} \left[\frac{N_a}{N_d} \right] \left[\frac{1}{N_a + N_d} \right] \right\}^{1/2}$$

↑ same as using x_p

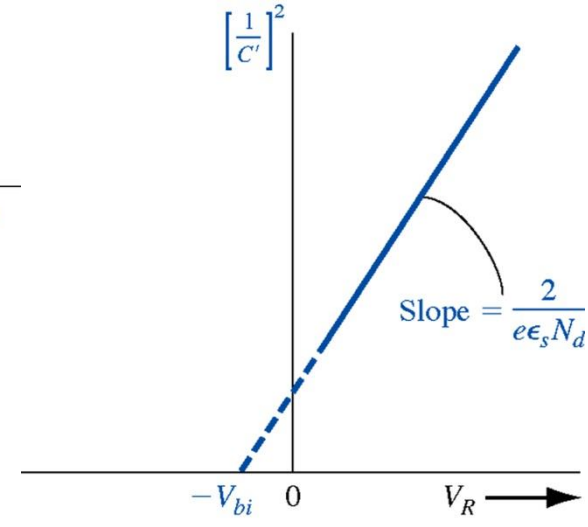
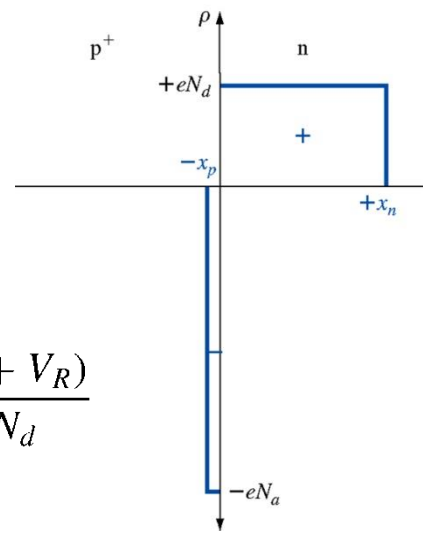


One-sided Junction (p^+n junction for $N_a \gg N_d$)

$$W \approx \left\{ \frac{2\epsilon_s(V_{bi} + V_R)}{eN_d} \right\}^{1/2}$$

$$x_p \ll x_n \quad W \approx x_n$$

$$C' \approx \left\{ \frac{e\epsilon_s N_d}{2(V_{bi} + V_R)} \right\}^{1/2} \Rightarrow \left(\frac{1}{C'} \right)^2 = \frac{2(V_{bi} + V_R)}{e\epsilon_s N_d}$$



Linearly Graded Junctions

Junction made by diffusion can be regarded as linearly graded junction in the metallurgical point.

$$\rho(x) = eax \quad \frac{dE}{dx} = \frac{\rho(x)}{\epsilon_s} = \frac{eax}{\epsilon_s}$$

$$E = \int \frac{eax}{\epsilon_s} dx = \frac{ea}{2\epsilon_s} (x^2 - x_0^2) \quad \leftarrow E(-x_0) = E(+x_0) = 0$$

$$\phi(x) = - \int E dx = \frac{-ea}{2\epsilon_s} \left(\frac{x^3}{3} - x_0^2 x \right) + \frac{ea}{3\epsilon_s} x_0^3 \quad \leftarrow \phi(-x_0) = 0$$

$$\phi(x_0) = \frac{2}{3} \cdot \frac{eax_0^3}{\epsilon_s} = V_{bi}$$

For reverse biased junction,

$$x_0 = \left\{ \frac{3}{2} \cdot \frac{\epsilon_s}{ea} (V_{bi} + V_R) \right\}^{1/3}$$

$$C' = \frac{dQ'}{dV_R} = (eax_0) \frac{dx_0}{dV_R} = \left\{ \frac{ea\epsilon_s^2}{12(V_{bi} + V_R)} \right\}^{1/3}$$

